Claims:

1. A resist composition comprising one or more basic compounds selected from those represented by the following formula (I):

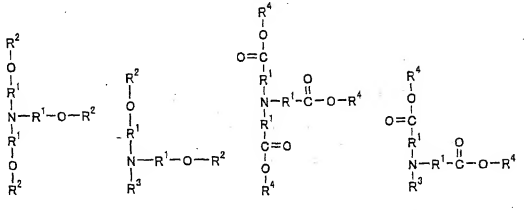
$$N(X)_n(Y)_{3-n} \quad (I)$$

wherein, n stands for 1, 2 or 3; side chains Xs are the same or different and each independently represents $-R^1-O-R^2$ or $-R^1-C(=O)-O-R^{61}$, in which R^1s are the same or different and each independently represents an alkylene group of 1 to 5 carbon atoms, R^2s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl or ester group, and R^{61}s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring, or R^1 and R^2, or R^1 and R^{61} in the same side chain may be coupled together to form a ring; and side chains Ys are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain an ether or hydroxyl group.

2. A resist composition according to claim 1, wherein n

in the formula (I) stands for 1 or 2.

3. A resist composition comprising one or more basic compounds selected from those represented by the following formulas (1) to (4).

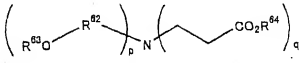


(1) (2) (3) (4)

wherein, R^1s are the same or different and each independently represents a C_{1-5} alkylene group, R^2s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl group or an ester group, R^3 represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxyl or ether group, and R^4s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl, ester or ether group.

4. A resist composition comprising one or more basic

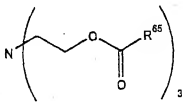
compounds selected from those represented by the following formula (II):



(II)

wherein, R^{62} represents a linear or branched alkylene group of 1 to 5 carbon atoms, p stands for 0, 1 or 2 with the proviso that p+q=3, R^{63}s are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group and R^{64}s are the same or different and each independently represents a linear, branched or cyclic alkyl group which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring.

5. A resist composition comprising one or more basic compounds selected from those represented by the following formula (III):



(III)

wherein R^{65}s are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group.

6. A resist composition according to claim 1, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

7. A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

8. A resist composition according to claim 3, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

9. A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic

functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

10. A resist composition according to claim 5, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

11. A resist composition according to claim 6, further comprising a dissolution inhibitor.

12. A resist composition according to claim 7, further comprising a dissolution inhibitor.

13. A resist composition according to claim 8, further comprising a dissolution inhibitor.

14. A resist composition according to claim 9, further comprising a dissolution inhibitor.

15. A resist composition according to claim 10, further comprising a dissolution inhibitor.

16. A resist composition according to claim 1, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

17. A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

18. A resist composition according to claim 3, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

19. A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

20. A resist composition according to claim 5, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.